

**AMENDMENTS TO THE CLAIMS:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

**LISTING OF CLAIMS:**

1. (Previously Presented) A component of a plasma processing apparatus, comprising:

a first member bonded to a second member, the first member including a plurality of through apertures having a first portion and a second portion wider than the first portion; and

a plurality of first fastener members each mounted in an aperture of the first member, each first fastener member including a head configured to prevent rotation of the first fastener members relative to the first member, the head having a bearing surface facing a surface that at least partially defines the second portion of the aperture.

2. (Currently Amended) The component of Claim 1, wherein the first fastener members are T-nuts having a T-shape and ~~with~~ internal threads.

3. (Previously Presented) The component of Claim 1, wherein the surface that at least partially defines the second portion of the aperture is a second bearing surface and the bearing surface of each of the first fastener members is bonded with an elastomer to the second bearing surface.

4. (Currently Amended) The component of Claim 1, further comprising:  
a temperature-controlled top plate on the first member, adjacent the first portion of the apertures of the first member, and including a plurality of through openings each aligned with a respective aperture in the first member; and  
a plurality of second fastener members each engaged with a respective first fastener member to secure the first member to the top plate.
5. (Original) The component of Claim 1, wherein each of the first fastener members comprises a rectangular shaped head.
6. (Previously Presented) The component of Claim 1, wherein each of the first fastener members includes a non-circular shaped head.
7. (Original) The component of Claim 1, wherein the first member comprises a plate made of graphite, and the second member comprises a showerhead electrode made of silicon.
8. (Previously Presented) The component of Claim 1, wherein the second member comprises an inner silicon electrode and a segmented outer silicon electrode, and the first member comprises a graphite backing plate secured to the inner silicon electrode and a graphite backing ring secured to the outer silicon electrode.

9. (Original) The component of Claim 4, wherein (i) each of the first fastener members comprises internal threads, and each of the second fastener members comprises external threads engaged with the internal threads of a respective first fastener member, or (ii) each of the first fastener members comprises external threads, and each of the second fastener members comprises internal threads engaged with the external threads of a respective first fastener member.

10. (Previously Presented) A component of a plasma processing apparatus, comprising:

a ~~first part~~ second member including an attachment surface and an exposed surface adapted to be exposed to an interior of a plasma processing chamber;

a ~~second part~~ first member including a first surface spaced from a second surface, the first surface being bonded to the attachment surface of the ~~first part~~ second member, the ~~second part~~ first member including axially extending apertures extending between the first surface and the second surface, each of the apertures including a first portion opening in the first surface and a second portion opening in the second surface, the first portion being wider in a transverse direction than the second portion; and

fastener members located in the second portions of the apertures.

11. (Currently Amended) The component of Claim 10, further comprising:

a third ~~part~~ member adjacent the second surface of the ~~second part~~ first member and including through openings aligned with the apertures in the ~~second part~~ first member; and

connectors located in the openings, the connectors being detachably engaged with the fastener members such that the third part member is detachable from the ~~second part~~ first member.

12. (Currently Amended) The component of Claim 10, wherein the first part second member is a showerhead electrode, and the ~~second part~~ first member is a backing plate.

13. (Currently Amended) The component of Claim 11, wherein the fastener members are T-nuts having a T-shape, and the connectors include external threads.

14. (Previously Presented) The component of Claim 10, wherein the second portions of the apertures comprise at least one load-bearing surface extending in the transverse direction, and the fastener members comprise at least one surface bonded to the load-bearing surface.

15. (Currently Amended) The component of Claim 10, wherein the fastener members are T-nuts having a T-shape.

16. (Currently Amended) The component of Claim 11, wherein the first portions of the apertures are round holes having diameters larger than diameters of openings in the third part member.

17. (Original) A showerhead electrode assembly for a plasma processing apparatus, comprising:

a silicon electrode having gas injection openings;

a graphite backing member secured to the silicon electrode, the backing member including a plurality of through apertures each having a first portion and a second portion wider than the first portion;

a top plate including a plurality of through openings each of which is aligned with a respective aperture in the backing member;

a plurality of first fastener members, each first fastener member being mounted in a respective aperture of the backing member, the first fastener member including a bearing surface facing a surface at least partially defining the second portion of the apertures; and

a second fastener member engaged with each first fastener member to secure the backing member to the top plate.

18. (Previously Presented) The showerhead electrode assembly of Claim 17, wherein the head of each of the first fastener members comprises a bearing surface adhesively bonded to the bearing surface of the aperture.

19. (Original) The showerhead electrode assembly of Claim 17, wherein the second portion of each aperture is configured to prevent rotation of the first fastener member relative to the backing member.

20. (Original) The showerhead electrode assembly of Claim 17, wherein the silicon electrode comprises an inner member and a segmented outer member, and the backing member comprises a backing plate secured to the inner member and a backing ring secured to the outer member.

21. (Original) The showerhead electrode assembly of Claim 17, wherein (i) each of the first fastener members comprises internal threads, and each of the second fastener members comprises external threads engaged with the internal threads of a respective first fastener member, or (ii) each of the first fastener members comprises external threads, and each of the second fastener members comprises internal threads engaged with the external threads of a respective first fastener member.

22. (Withdrawn) A method of making a component of a plasma processing apparatus, comprising:

mounting a plurality of first fastener members in a plurality of apertures of a first member, each aperture including a first portion and a second portion wider than the first portion, each first fastener member including a bearing surface facing a surface that at least partially defines the second portion of the aperture, and a head disposed in the second portion of an aperture; and

bonding the first member to a second member;

the head of each of the first fastener members being configured to prevent rotation of the first fastener members relative to the first member.

23. (Withdrawn) The method of Claim 22, further comprising fastening the first member to a top plate including a plurality of through openings each of which is aligned with a respective aperture of the first member, the fastening including inserting a second fastener member in openings of the top plate such that each second fastener member engages a respective first fastener member to secure the first member to the top plate.

24. (Withdrawn) The method of Claim 22, wherein the first fastener members are T-nuts.

25. (Withdrawn) The method of Claim 22, further comprising, before the mounting, bonding the head of each of the first fastener members to the bearing surface that partially defines the second portion of the aperture.

26. (Previously Presented) A component of a plasma processing apparatus, comprising:

a first member bonded to a second member, the first member including a plurality of through apertures having a first portion and a second portion wider than the first portion; and

a plurality of first fastener members each mounted in an aperture of the first member, each first fastener member including a head configured to prevent rotation of the first fastener members relative to the first member and an externally threaded end portion opposite the head, the head having a bearing surface facing a surface that at least partially defines the second portion of the aperture.

27. (Currently Amended) The showerhead electrode assembly of Claim 17, wherein the first fastener members are T-nuts having a T-shape.

28. (Currently Amended) The component of Claim 11, wherein the third ~~part~~ member is a temperature-controlled top plate.

29. (Currently Amended) The showerhead electrode assembly of Claim 17, wherein the top plate is on the backing member, adjacent the first portion of the apertures of the backing member, and is temperature-controlled.

30. (Previously Presented) The showerhead electrode assembly of Claim 17, wherein the backing member comprises a first surface and a second surface opposite the first surface, the first surface is secured to the silicon electrode and the second surface is secured to the top plate.